

AMENDMENTS TO THE CLAIMS

Claim 1 (currently amended): A method of forming a layer of fixed geometry for use in a device having at least two device layers, the method comprising the steps of:

providing a substrate for the device;

depositing a layer of photoresist on said substrate;

forming openings in the layer of photoresist that expose portions of the substrate; and

depositing a precursor ~~in a substantially liquid form~~ in the openings of the photoresist to form at least one layer of fixed geometry, wherein said depositing step is performed using chemical vapor deposition, and wherein a gas phase reaction during the chemical vapor deposition results in a product that condenses to form the precursor in a substantially liquid form on walls of the openings.

Claims 2-7 (canceled)

Claim 8 (original): The method of forming a layer of fixed geometry as set forth in claim 1, wherein the device is a flat panel display composed of a cathode and a faceplate;

wherein the faceplate is composed of the substrate provided in said providing step and a conductive layer; and

wherein the at least one layer of fixed geometry is formed as at least one spacer on the faceplate of the flat panel display for maintaining a distance between the cathode and the faceplate in the flat panel display.

Claim 9 (original): The method of forming a layer of fixed geometry as set forth in claim 8, wherein said depositing step further comprises the substep of forming a plurality of spacers uniformly deposited on the substrate.

Claim 10 (original): The method of forming a layer of fixed geometry as set forth in claim 8, wherein said depositing step further comprises the substep of forming at least one spacer having a circular cross-sectional shape normal to a top surface of the substrate.

Claim 11 (original): The method of forming a layer of fixed geometry as set forth in claim 8, wherein said depositing step further comprises the substep of forming at least one spacer having an approximately I-shaped spacer.

Claim 12 (original): The method of forming a layer of fixed geometry as set forth in claim 8, wherein said depositing step further comprises the substep of forming at least one spacer having an approximately T-shaped spacer.

Claims 13-46 (canceled)

Claim 47 (currently amended): A method of forming a layer of fixed geometry for use in a device having at least two device layers, the method comprising the steps of:

providing a substrate for the device; and

depositing a sol-gel precursor ~~in a substantially liquid form~~ on a top surface of the substrate to form at least one layer of fixed geometry, wherein said depositing step is performed using chemical vapor deposition, and wherein a gas phase reaction during the chemical vapor deposition results in a product that condenses to form the precursor in a substantially liquid form on walls of the openings.

Claim 48 (previously presented): The method of forming a layer of fixed geometry as set forth in claim 47, wherein the device is a flat panel display composed of a cathode and a faceplate;

wherein the faceplate is composed of the substrate provided in said providing step and a conductive layer; and

wherein the at least one layer of fixed geometry is formed as at least one spacer on the faceplate of the flat panel display for maintaining a distance between the cathode and the faceplate in the flat panel display.

Claim 49 (previously presented): The method of forming a layer of fixed geometry as set forth in claim 48, wherein said depositing step further comprises the substep of forming a plurality of spacers uniformly deposited on the substrate.

Claim 50 (previously presented): The method of forming a layer of fixed geometry as set forth in claim 48, wherein said depositing step further comprises the substep of forming at least one spacer having a circular cross-sectional shape normal to a top surface of the substrate.

Claim 51 (previously presented): The method of forming a layer of fixed geometry as set forth in claim 48, wherein said depositing step further comprises the substep of forming at least one spacer having an approximately I-shaped spacer.

Claim 52 (previously presented): The method of forming a layer of fixed geometry as set forth in claim 48, wherein said depositing step further comprises the substep of forming at least one spacer having an approximately T-shaped spacer.